NANO-C, INC. AND IRRESISTIBLE MATERIALS, LTD. ENTER INTO A STRATEGIC BUSINESS RELATIONSHIP TO ADVANCE MUTUAL BUSINESS INTERESTS

Nano-C acquires LiquidCarbon™ patent portfolio from Irresistible Materials, Ltd.

Irresistible Materials to focus exclusively on driving the development and commercialization of its innovative EUV photoresist material

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Nano-C, Inc., a leader in the development of nanostructured carbon, electronic materials, and specialty chemicals, has acquired an advanced lithography patent portfolio from **Irresistible Materials, Ltd.** (IM), a leader in the development of novel photoresist materials for extreme ultraviolet (EUV) lithography.

Nano-C and IM have been long-term partners in the development of leading-edge lithography materials. Nano-C's acquisition of IM's novel LiquidCarbon™ patent portfolio enables the company to develop and supply high-carbon mask solutions to leading global semiconductor manufacturing companies. In turn, this will enable IM to have a strong focus on the R&D, manufacturing, and business development related efforts for its patented Multi-Trigger Resist (MTR™) targeted at the semiconductor industry's leading Integrated Device Manufacturers (IDMs) and foundries for low-NA and high-NA EUV lithography. The terms of the transaction are not being disclosed.

As high-carbon content formulations, LiquidCarbon™ provides the rigid, ultra-thin mask necessary to etch complex structures for manufacturing chips for high power AI computing. With carbon content able to exceed 90%, these high value formulations can achieve carbon loading similar or exceeding CVD carbon processes. LiquidCarbon™ can be tuned along several key parameters in terms of concentration, solvents and chemical functionalization to optimize the most challenging lithography process demands.

IM's MTR material is a patented small-molecule resist platform, designed with molecular dimensions up to 10 times smaller than those of conventional polymer-based resists to enable superior resolution and pattern fidelity. The MTR chemistry mechanism is being developed with the goal of minimizing blurring while achieving both reduced line-edge and line-width roughness (LER/LWR) and higher sensitivity for improved yield, addressing one of the key trade-offs in advanced EUV patterning. By targeting improved resist efficiency, the MTR platform aims to support faster processing and significantly lower CoO compared with conventional resist technologies.

"Both Nano-C and Irresistible Materials are very well positioned to address the rapidly evolving demands of high-performance lithography materials. This new strategic agreement will allow both companies to accelerate the development and commercialization of these novel materials," said Viktor Vejins, CEO of Nano-C, Inc. "This LiquidCarbon™ product platform leverages the

company’s global leadership in industrial scale nanocarbon production as these products are uniquely based on Nano-C’s core fullerene materials; which on their own are 100% carbon and can be formulated in fab-ready solvents to meet the stringent quality requirements in advanced chip manufacturing."

"We are very pleased to have found a good home for our valuable LiquidCarbon™ patent portfolio which will serve as a strong complement to Nano-C’s advanced nanocarbon capabilities," said Dinesh Bettadapur, Chief Executive Officer, Irresistible Materials. "This enables us to move forward rapidly with getting our proprietary MTR material ready for sampling and manufacturing scale up to meet the EUV lithography process needs of the industry’s leading chip manufacturers.”

About Nano-C, Inc.
Nano-C is a leading developer of nanostructured carbon, electronic materials, and specialty chemicals. Through its expertise in chemistry, Nano-C enables the creation of smaller, lighter, and more durable devices across the electronics, energy, and semiconductor industries. Nano-C’s mission is to play a key role in enabling applications of these materials and is committed to their responsible development and use.
Nano-C operates from its facility in Westwood, Massachusetts, with a growing portfolio of products, patents, knowhow, and manufacturing assets. Nano-C is proud to be an **ISO-9001 Certified Supplier**.

For more information about Nano-C, please visit **https://www.nano-c.com.**

For more information about Nano-C’s LiquidCarbon™ product platform, please visit **https://www.nano-c.com/liquidcarbon**

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About Irresistible Materials
Irresistible Materials is a pioneering electronic materials technology company specializing in developing advanced photoresists for next-generation EUV lithography in semiconductor manufacturing. Its patented photoresist material called Multi-Trigger Resist (MTR™) offers superior imaging performance for low-NA and high-NA EUV compared to competing solutions across several key criteria, including resolution, line width roughness (LWR), line edge roughness (LER), sensitivity, absorbance, defectivity, and etch resistance. As a result, IDM and foundry customers can realize the benefits of higher manufacturing yields and significantly lower cost of ownership (CoO) for both logic and memory devices across multiple applications. Irresistible Materials is headquartered in Birmingham, UK, and has numerous issued patents and patent filings covering its MTR™ platform and related technologies. For more information, visit www.irresistiblematerials.com

Media Contacts

For Irresistible Materials:
Angie Kellen
Open Sky Communications
Phone: +1 408.829.0106
E-mail: akellen@openskypr.com

For Nano-C:
Darren Bischoff
Nano-C, Inc
E-mail: nanocpress@nano-c.com